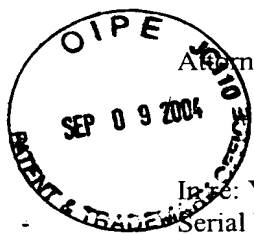


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Attorney's Docket No. 5649-1129

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re: Yun et al.

Serial No.: 10/629,280

Filed: July 29, 2003

For: GATES STRUCTURES IN NONVOLATILE MEMORY DEVICES HAVING
CURVED SIDEWALLS FORMED USING OXYGEN PATHWAYS AND
METHODS OF FORMING SAME

Group Art Unit: 2818

Examiner: Thao P. Le

Confirmation No.: 5702

Date: September 3, 2004

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

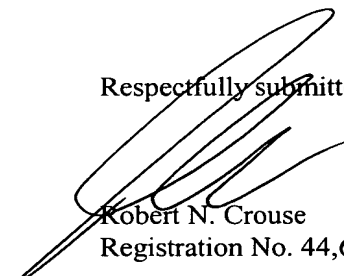
INFORMATION DISCLOSURE STATEMENT

Sir:

Attached is Form PTO-1449 listing documents cited in the Korean Office Action for the corresponding Korean Application Number 2002-0054460. Each document listed on the attached PTO-1449 was first cited in a communication from a foreign patent office in a counterpart foreign application not more than three months prior to the filing of this Statement. A copy of each document including the Korean Office Action, is enclosed.

No fee is believed due; however, the Commissioner is hereby authorized to charge any deficiency or credit any refund to Deposit Account No. 50-0220.

Respectfully submitted,


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I hereby certify that this correspondence is being deposited with the United States Postal Service with sufficient postage as first class mail in an envelope addressed to: Mail Stop Amendment, Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450 on September 3, 2004.


Elizabeth V. Porter

5649-1129

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01/31/2002

English Translation of Korean Office Action; Korean Patent Application No. 10-2002-0054460, Date of Korean Office Action 7/30/2004.

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.